



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Patent Application Serial No. 10/643,680
Filing Date August 18, 2003
Inventorship Brenda D. Kraus et al.
Assignee Micron Technology, Inc.
Group Art Unit 1762
Examiner Brian K. Talbot
Attorney's Docket No. MI22-2310
Title: Atomic Layer Deposition Methods of Forming Conductive Metal Nitride
Comprising Layers

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References - See Attached Form PTO-1449

The attached form PTO-1449 is submitted in compliance with 37 CFR §1.56. No copies of any cited U.S. patents or U.S. published applications are included herewith. Copies of all other cited art are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

A check in the amount of \$180.00 is enclosed to cover the fee specified under 37 C.F.R. § 1.17(p).

Respectfully submitted,

Dated: 1-10-07

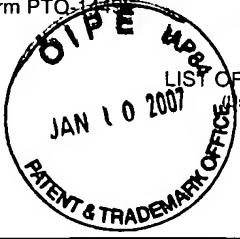
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Form PTO-1449 		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2310		SERIAL NO. 10/643,680		
		LIST OF ART CITED BY APPLICANT <small>(use several sheets if necessary)</small>		APPLICANT: Kraus et al.				
				FILING DATE August 18, 2003		GROUP 1762		
		U.S. PATENT DOCUMENTS						
*Examiner's Initials		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
	AA	6,203,613	03/01	Gates et al.				
	AB	10/196,814	07/02	Kyung-In				
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
	AJ						Yes	No
	AK							
	AL							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AM		Park et al., "Plasma-Enhanced Atomic Layer Deposition of Tantalum Nitrides Using Hydrogen Radicals as a Reducing Agent", Electrochemical and Solid-State Letters, 4 (4) C17-C19, The Electrochemical Society, Inc. (2001).					
	AN							
	AO							
EXAMINER		DATE CONSIDERED						
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

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